Photonic Curing System

Technical Specifications:

1) Photonic pulse repetition rate: > 6 Hz with radiant exposure 1 J/cm² & > 2 Hz for 5 J/cm²
2) Uniform beam intensity and angle control
3) Flexibility in changing the intensity, exposure length and pulse shape.
4) Sensor for measuring the radiative exposure, data acquisition system & software.
5) Minimum exposure area per pulse: 110 cm² for 150 mm wide lamp, 235 cm² for 300 mm wide lamp.
6) Porous vacuum chuck.
7) Temperature range: 15⁰C-350⁰C
8) Sealed chamber with removable vacuum chamber lid with quartz windows.
9) Integrated bolometer.
10) Should have successfully done the annealing of organic-inorganic hybrid perovskite solar cells with this system.